

GAS SUPPLY SYSTEM, GAS SUPPLY CONTROL METHOD AND GAS REPLACEMENT METHOD

ABSTRACT

Throughput of the processing can be improved. A gas supply system includes a plurality of element devices which constitute the gas supply system and a base 212 on which the plurality of element devices are disposed. Some of the element devices are disposed on a surface 212a of the base 212, and the others are disposed on a surface 212b of the base 212, which is opposite to the surface 212a of the base 212. The plurality of element devices may be implemented by, for example, a flow rate controller FD and a secondary valve FV2. The secondary valve FV2 is disposed on the surface 212b, which is opposite to the surface 212a of the base 212 where the flow rate controller FD is disposed.

Figure 1